

## The performance of sulphurized TiO<sub>2</sub>/In<sub>2</sub>S<sub>3</sub>/CuInSe<sub>2</sub> solar cells.

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**Abstract** – An In<sub>2</sub>S<sub>3</sub> buffer layer has been prepared by spray – pyrolysis on TiO<sub>2</sub>/TCO glass substrates. On top of them CuInSe<sub>2</sub> films have been electrodeposited from a single bath solution. CISE films have been deposited potentiostatically using a deaerated electrolyte at different potentials. Each layer has been studied by electron microscopy, electrochemical impedance and optical absorption spectroscopy. After a thermal annealing stage in a sulphur atmosphere at 550 °C for 10-30 minutes the crystallinity of the resulting chalcogenide is excellent. In particular the nominal crystal structure and the band gap of 1.4 eV are found and a clear photoconductivity response is obtained.

TiO<sub>2</sub> has been prepared by spray-pyrolysis, using TCO glass as substrate. The temperature of the hot plate is set between 350 – 375 °C, later increased to 450 °C for 30 minutes to enhance the crystallinity.

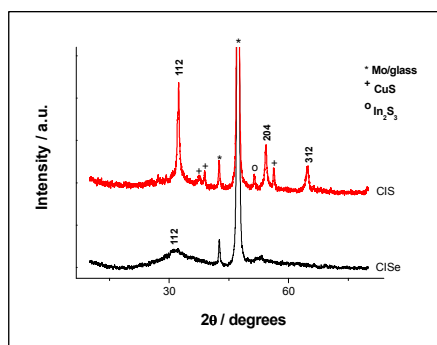
In<sub>2</sub>S<sub>3</sub> has been sprayed on top of this layer. The hot plate is set on 300 °C and kept 30 minutes after the spray. The In/S ratio was fixed to 1.2/8.

CuInSe<sub>2</sub> (CISE) is then electrodeposited at room temperature from a single aqueous bath containing CuCl<sub>2</sub>, InCl<sub>3</sub> and SeO<sub>2</sub>. The deposition is potentiostatic, with the potential ranging from -0.8 to -1.1 V vs. SCE. Homogenous, black films of CISE are thus obtained.

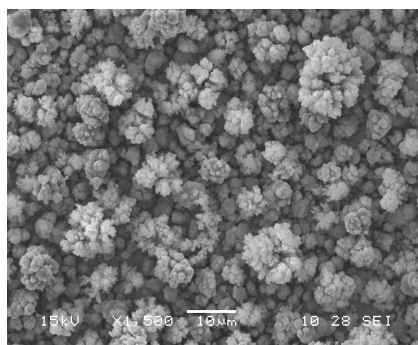
The complete device was annealed at 550 °C varying the time between 10-30 minutes. 0.5 g of sulphur are placed in the annealing chamber and heated at 350 °C (melting starts at around 200-250 °C). The samples are placed in a “cold zone” (100 °C) of the tube and when the temperature reaches 550 °C they are moved to the “annealing zone” and kept there for a fixed time. Then they are moved back to the cold zone of the tube. Nitrogen is flashed during all the annealing. This thermal treatment changes the CuInSe<sub>2</sub> structure to a CuInS<sub>(2-x)</sub>Se<sub>x</sub> (CISSe). To evaluate the transformation from CISE to CISSe films have been deposited on Mo substrates and annealed in the same conditions as those of the films deposited on TCO/TiO<sub>2</sub>/In<sub>2</sub>S<sub>3</sub> substrates.

After the annealing treatment, the samples are etched in 0.5 mol/L KCN for several minutes to remove secondary phases (CuSe or Cu<sub>2</sub>Se) that are detrimental for the devices. X-ray analysis shows a complete transformation of the CuInSe<sub>2</sub> to CuInS<sub>2</sub> composition as is indicated in the change in the (112) amorphous CISE peak to a high crystallinity (112) CIS structure. This is a key step which governs the final composition of the chalcogenide layer and determines the overall performance of the solar cell.

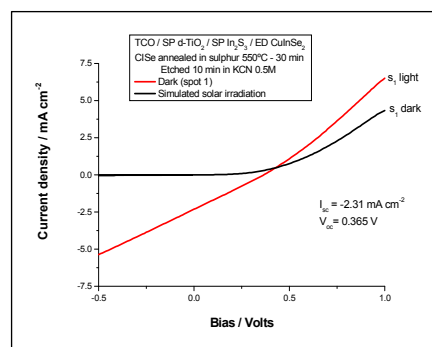
Figure 1 presents XRD patterns of the as deposited CISE films on Mo/glass substrate and the transformation that occurs after annealing in sulphur at 550 °C during 30 minutes. As can be seen, a complete transformation takes place. SEM micrographs of CIS films show an homogenous material with regular-size particles (Figure 2). A promising solar cell device is shown in Figure 3. A Xe lamp was used a light source. In spite of the low values of the open circuit potential (V<sub>oc</sub>) and the short-circuit current density (J<sub>sc</sub>) this is a starting-point result, from which we can continue working in improving the conversion efficiency.



**Figure 1:** XRD patterns of CISE films deposited on Mo/glass substrates. (-) As deposited. (-) Annealed in sulphur at 550 °C during 30 min.



**Figure 2:** SEM image of annealed CISE precursor. The CISE film was deposited at -1 V vs. SCE during 1 hour, annealed at 550 °C for 30 minutes in sulphur atmosphere.



**Figure 3:** I-V curve (dark vs. illumination) performed on TCO/TiO<sub>2</sub>/In<sub>2</sub>S<sub>3</sub>/CuInSe<sub>2</sub>. The CISE film was deposited at -1.1 V vs. SCE during 1 hour, annealed in sulphur minutes.